



Form 14-16 (Modified)

**Information Disclosure  
Statement By Applicant**

(Use Several Sheets if Necessary)

Atty Docket No.  
LAM1P152 P0692

Application No.:  
09/782,446

Applicant:

HO et al.

Filing Date

February 12, 2001

Group

1746

**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	J							
	K							
	L							
	M							
	N							

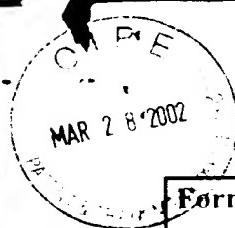
**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication		
LV	O	U.S. Patent Application Serial No. 09/782,185, entitled "Unique Process Chemistry for Etching Organic Low-K Materials", filed February 12, 2001		
LV	P	U.S. Patent Application Serial No. 09/782,678, entitled "Post-Etch Photoresist Strip with O <sub>2</sub> and NH <sub>3</sub> for Organosilicate Glass Low-K Dielectric Etch Applications", filed February 12, 2001		
LV	Q	U.S. Patent Application Serial No. 09/782,437, entitled "Use of Hydrocarbon Addition for the Elimination of Micromasking during Etching of Organic Low-K Dielectrics", filed February 12, 2001		

Examiner

Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.


**Form 1449 (Modified)**
**Information Disclosure  
Statement By Applicant**

(Use Several Sheets if Necessary)

 Atty Docket No.  
**LAM1P152/P0692**

 Application No.:  
**09/782,446**

Applicant:

**HO et al.**

Filing Date

**February 12, 2001**

Group

**1746**
**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
L v	A	6,037,255	03/14/00	Hussein et al.	438	675	05/12/99
	B	6,080,529	06/27/00	Ye et al.	430	318	10/19/98
	C	6,153,511	11/28/00	Watatani	438	623	06/25/99
	D	6,174,796	01/16/01	Takagi et al.	438	622	12/30/98
L v	E	6,194,128	02/27/01	Tao et al.	430	313	09/17/98
	F						
	G						
	H						
	I						

**Foreign Patent or Published Foreign Patent Application**

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
J								
K								
L								
M								
N								

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 TC 1700

**Other Documents**

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	O	
	P	
	Q	
Examiner	LAM1P152	Date Considered 1/12/02

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.